EE 121B Mid-term Examination Spring 2013

Name _____

Open Book Assume T=300K and the substrate is silicon and $n_i = 1.5 \times 10^{10} cm^{-3}$



a) What is the neutral base width of the device with the DC biases as indicated? (9 points)

$$V_{bi,BE} \approx \frac{kT}{q} \ln \frac{N_{AB}N_{DE}}{n_i^2} \approx 1.09V$$
$$V_{bi,BC} \approx \frac{kT}{q} \ln \frac{N_{AB}N_{DC}}{n_i^2} \approx 0.868V$$

Thus,

$$\begin{aligned} x_p &\approx \sqrt{\frac{2\epsilon_{Si}N_{DE}(V_{bi,BE} - V_{BE})}{qN_{AB}(N_{AB} + N_{DE})}} \approx 22.4nm\\ x'_p &\approx \sqrt{\frac{2\epsilon_{Si}N_{DC}(V_{bi,BE} + V_{CB})}{qN_{AB}(N_{AB} + N_{DC})}} \approx 11nm \end{aligned}$$

(6')

And,

$$W_B \approx L_B - x_p - x'_p = 116.6nm$$

(3')

b) What is the value of I_C , I_E , and I_B ? (17 points)

Using Einstein relation, we have diffusion constant and diffusion length

$$D_{nB} = \frac{kT}{q} \mu_{nB} \approx 10.4 \ cm^2/s \text{ and } L_{nB} = \sqrt{D_{nB}\tau_{nB}} \approx 32\mu m$$
$$D_{pE} = \frac{kT}{q} \mu_{pE} \approx 2.85 \ cm^2/s \text{ and } L_{pE} = \sqrt{D_{pB}\tau_{pB}} \approx 1.7\mu m$$
$$D_{pC} = \frac{kT}{q} \mu_{pC} \approx 24.6 \ cm^2/s$$

Using charge neutral, $x_n \approx x_p \frac{N_{AB}}{N_{DE}} \approx 0.04nm$, so we can approximate $W_E \approx L_E$.

Calculate ideal current for BE junction,

$$I_n(0) \approx \frac{qAD_{nB}n_i^2}{N_{AB}W_B} \left[\exp\left(\frac{qV_{BE}}{kT}\right) - 1 \right] \approx 1.8 \times 10^{-5}A$$
$$I_p(-W_D) \approx \frac{qAD_{nE}n_i^2}{N_{DE}W_E} \left[\exp\left(\frac{qV_{BE}}{kT}\right) - 1 \right] \approx 5.6 \times 10^{-9}A$$

while the recombination current is given by

$$I_{REC} \approx \frac{qAn_i \overline{W_{DBE}} \left(\exp \frac{qV_{BE}}{nkT} - 1 \right)}{\tau_{REC}} \approx \frac{qAn_i x_p \left(\exp \frac{qV_{BE}}{2kT} - 1 \right)}{10\tau_{REC}}$$
$$\approx 4.0 \times 10^{-10} A$$

(2')

So,

$$I_B \approx I_p(-W_D) + I_{REC} \approx 6.0 \times 10^{-9} A$$
$$I_E \approx I_n(0) + I_p(-W_D) + I_{REC} \approx 1.8 \times 10^{-5} A$$

and (5' for I_C +5' for I_E +5' for I_B)

$$I_C \approx I_E \approx 1.8 \times 10^{-5} A$$

c) What is the common emitter current gain, β_o ? (10 points)

$$\beta \approx \left[\frac{D_{pE} N_{AB} W_B}{D_{nB} N_{DE} W_E} + \frac{\overline{W_{DBE}} W_B N_{AB} \exp\left[-\frac{q V_{BE}}{kT} \left(\frac{n-1}{n}\right)\right]}{D_{nB} n_i \tau_{REC}} \right]^{-1} \\\approx [3.2 \times 10^{-4} + 2.2 \times 10^{-5}]^{-1} \approx (3.2 \times 10^{-4})^{-1} \approx 3000$$

(In this case, we ignore the contribution of the recombination current for simplicity) (5' for equation, 5' for calculation)

(e) What is the Early voltage? (10 points) $V_A \approx \frac{qW_B N_{AB}}{C_{DBC}} = \frac{qW_B N_{AB} W'_D}{\epsilon_{Si}} \approx 27V$ where $W'_D \approx \sqrt{\frac{2\epsilon_{Si}(V_{CB}+V_{bi,BC})(N_{DC}+N_{AB})}{qN_{DC}N_{AB}}} \approx 149$ nm

(5' for equation, 5' for calculation)

(f) What is base transit time τ_B ? (8 points)

Base transit time $\tau_B = \frac{W_B^2}{2D_{nB}} \approx 6.5 \text{ps}$

(5' for equation, 5' for calculation)

2 (a) If we want to increase β_o by 25% by reducing the base metallurgical width (which was originally 150nm), what is the new base metallurgical width? (10 points)

Again, if we ignore the recombination current,

$$\beta_0 \approx \frac{D_{nB} N_{DE} W_E}{D_{pE} N_{AB} W_B}$$

To increase β_0 25% by changing W_B ,

$$W_{\rm P} \approx 0.3$$

 $W_B \approx 0.8 W_{B0}$ So the new metallurgical width can be estimated by $L_B\approx 0.8W_{B0}+x_p+x_p'\approx 127nm$

(5' for equation, 5' for results)

(b) If instead, we want to increase β_o by 25% by reducing the base doping concentration, what is the new base doping? Use the graph below for mobility dependence on concentration. (12 points)



Again, if we ignore the recombination current,

$$\beta_0 \approx \frac{D_{nB} N_{DE} W_E}{D_{pE} N_{AB} W_B}$$

To increase β_0 by 25%, in first order, we can estimate

$$N_{AB} \approx 0.8 N_{AB0} \approx 8 \times 10^{17} cm^{-3}$$

However, since D_{nB} and W_B also change with N_{AB} , we need to iterate to get N_{AB} . As D_{nB} and W_B change slowly with N_{AB} (which is about 410 cm²/V · s and

 $W_B \approx L_B - x_p - x'_p \approx L_B - x_{p0} \cdot \sqrt{N_{AB0}/N_{AB}} - x'_p \cdot N_{AB0}/N_{AB} \approx 111nm$, iterate for N_{AB}

$$N_{AB} \approx 0.8 N_{AB0} \cdot \frac{W_{B0}}{W_B} \cdot \frac{D_{nB}}{D_{nB_0}} \approx 8.6 \times 10^{17} cm^{-3}$$

(6' for formula/equations, 3' for iteration, 3' for answer)

(c) What are the Early voltages for (a) and (b)? Discuss. (12 points) $V_A \approx \frac{qW_B N_{AB}}{C_{DBC}} = \frac{qW_B N_{AB} W'_D}{\epsilon_{Si}}$ In (a) $W_B = 0.8W_{B0}$, so $V_A \approx 0.8V_{A0} \approx 21.6V$ (4') In (b) $N_{AB} \approx 0.86N_{AB0}$, $W_B/W_{B0} \approx 0.95$, and $C_{DBC}/C_{DBC0} = W'_{D0}/W'_D \approx 1$, $V_A \approx 0.86 \cdot 0.95V_{A0} \approx 0.81V_A \approx 22V$ (4') In two cases, the early voltage reduces as the total charge of the base $W_P N_{PD}$

In two cases, the early voltage reduces as the total charge of the base $W_B N_{AB}$ decreases. And in both cases, V_A will be very similar as the change of C_{DBC} can be ignored. the only difference is caused by the mobility improvement when lowering the base doping (which causes $W_B N_{AB}$ to be different in two cases) (4')

(d) What are the base transit time for (a) and (b)? Discuss. (12 points) The base transit time is given by

$$\tau_B = \frac{W_B^2}{2D_{nB}}$$

In case (a), $W_B = 0.8W_{B0}$, so

$$\tau_B = \frac{W_B^2}{2D_{nB}} = 0.64\tau_{B0} \approx 4.2ps$$

(4')

In case (b), $W_B = 0.95W_{B0}$ and $D_{nB} \approx 1.03D_{nB0}$ $\tau_B = \frac{W_B^2}{2D_{nB}} \approx 0.88\tau_{B0} \approx 5.7ps$ (4')

Apparently, in case (a), τ_B is much smaller than the one in case (b), due to the reason that τ_B is proportional to the square of the neutral base width. Thus, given D_{nB} is somewhat a constant, the way to increase β by reducing W_B more will greatly improve the transit time, resulting in a better high frequency performance. (4')